

Minutes from OpenPICs WP 4 meeting 29-05-2017

Present: Longfei, Rui, Rob, Roel, Tjibbe, Rene, Robert, Weiming

Discussion/action points

Nr.	Description	Responsible
1.	Al-MQW <ul style="list-style-type: none"> The design will be ready in 1-2 weeks. The Al-Q will be calibrated in both Nanolab and Smart reactors. 	Weiming, Longfei
2.	Zn diffusion tests <ul style="list-style-type: none"> Get an empirical model based on more data points with the standard MPW layerstack. Quick diffusion test on a SiNx mask covered sample to check particles. 4 samples will be shipped to UK for SIMS measurement. Test with mask opening. Longfei will follow up on the design. 	Rene Longfei
3.	BCB planarization <ul style="list-style-type: none"> Planarization test has been done on the sample from Smart. Tjibbe is waiting for Tencor to be operational for the measurement. Lithography parameters have to be re-optimized for BCB. 	Tjibbe
4.	Stepper process <ul style="list-style-type: none"> FEM tests with AZ resist will be done in 1-2 weeks. 	Robert
5.	Etching process <ul style="list-style-type: none"> The new CH4-H2 recipe (optimized for ~3 degree side-wall angle in Smart's ICP) will be transferred to Nanolab after a few more fine-tuning. 2 Cl2-CH4-H2 recipes were tested, giving etch rates of 360 (@60C) and 250 (@200C) nm/min. No influence to the reactor is observed. Oxford has been contacted for suggestions of the next plans. 	Rui Longfei
6.	Planning and milestone list The milestone list with quantified criteria has been sent around. Each responsible person should check their own items. Upcoming due dates for milestones: M 3.1 (end June) Zn-diffusion time determined: ready for joint MPW validation. M 5.1 (end June) DUV lithography introduced to MPW.	Everyone Rene Smart

Next meeting: 13:30-15:00, 12-6-2017, Flux 10.177